



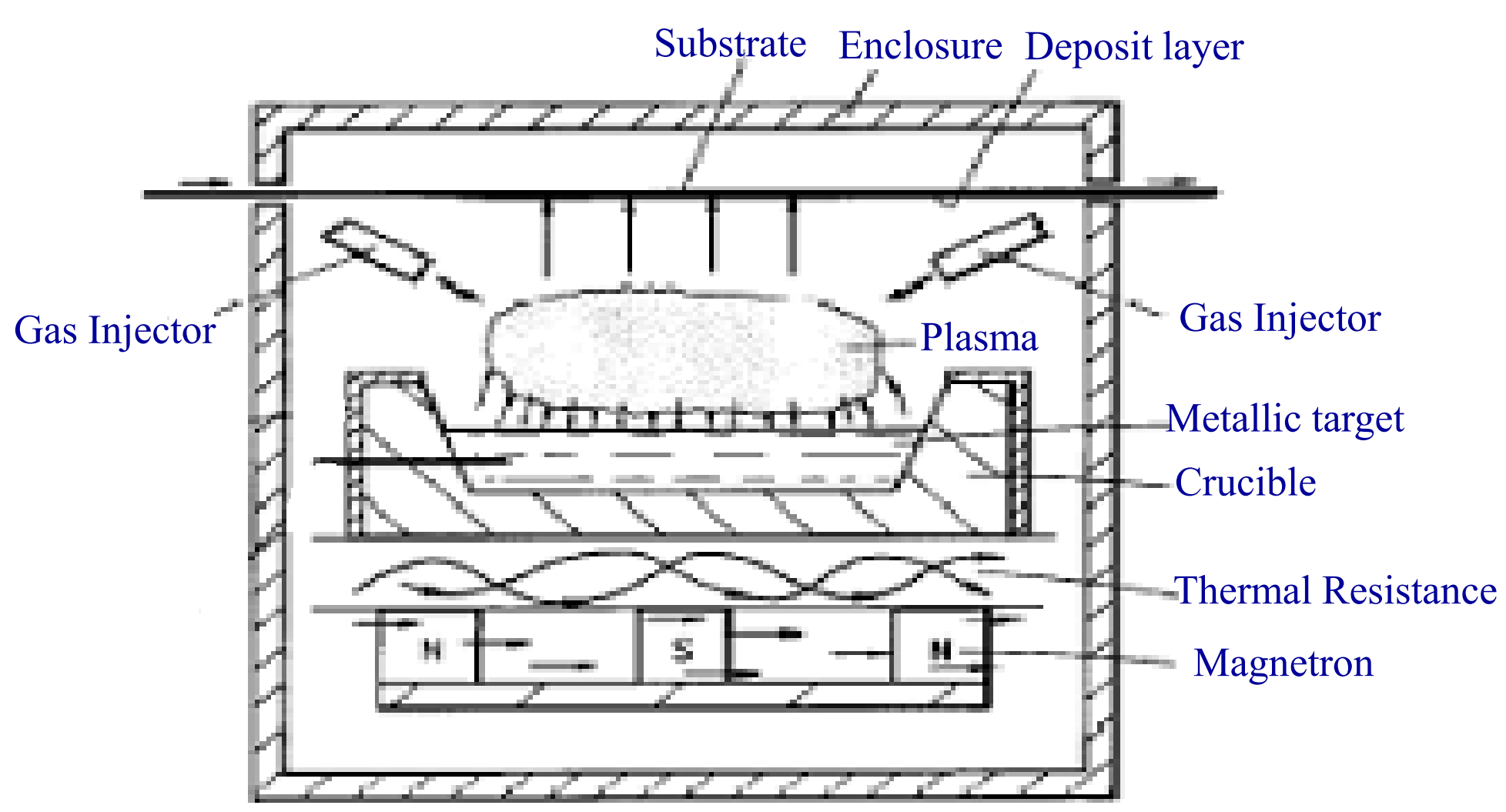
Modelling of continuous steel coating by Self-Induced Ion Plating (SIP)

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Self-Induced Ion Plating (European Patent N° 0780489)



➤ a new physical vapour deposition process to produce continuous coating of flat products in the steel industry

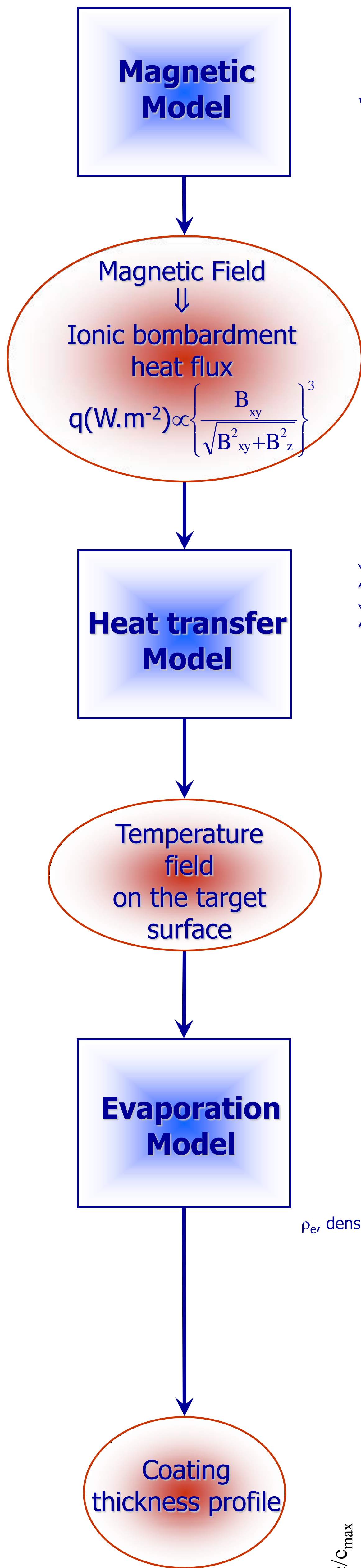
➤ a process based on the evaporation of a metallic target thanks to a magnetron sputtering system

Objective

Numerical simulation model of the SIP process

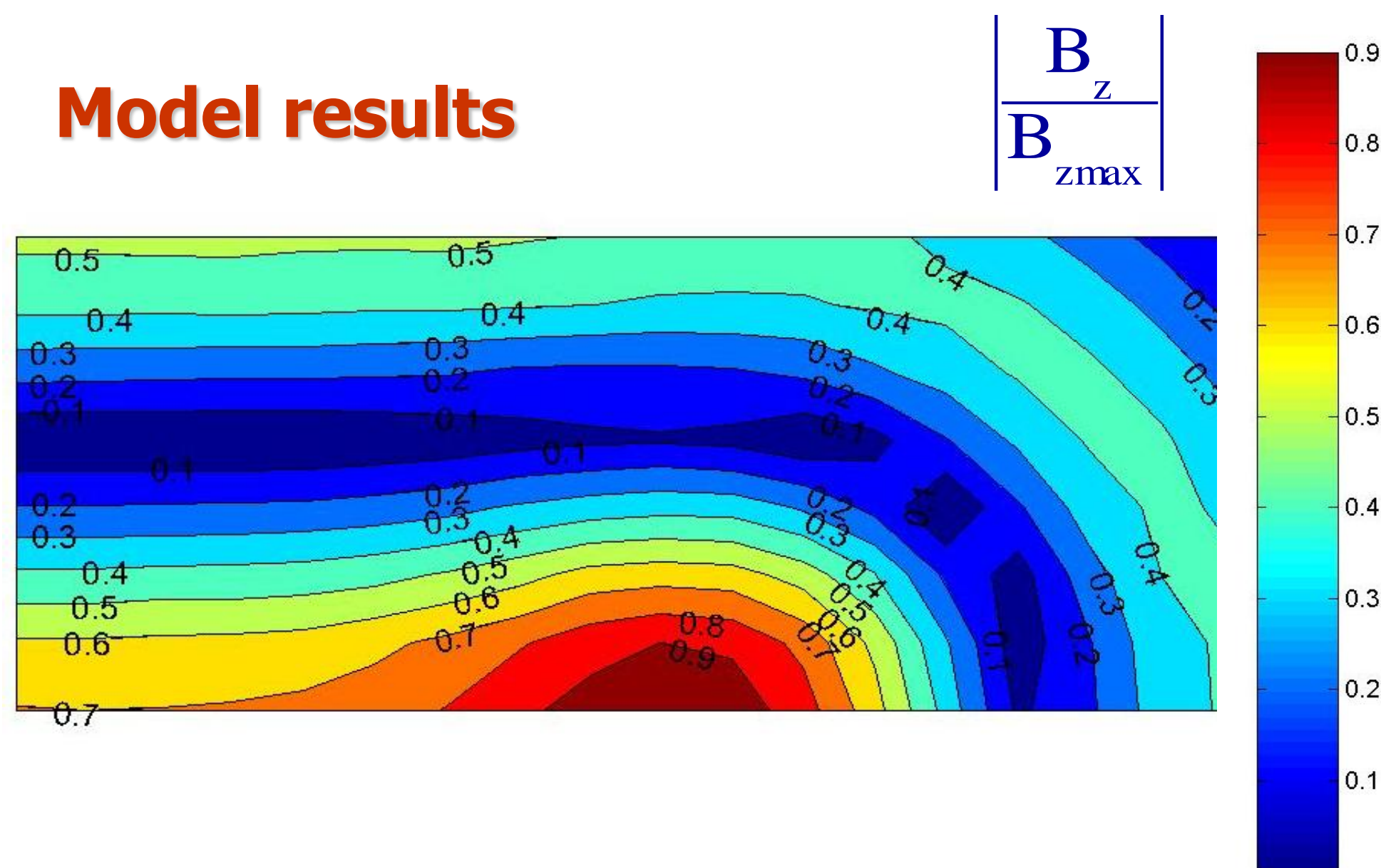
⇒ prediction of the coating thickness profile obtained on the substrate

Simulation models and results

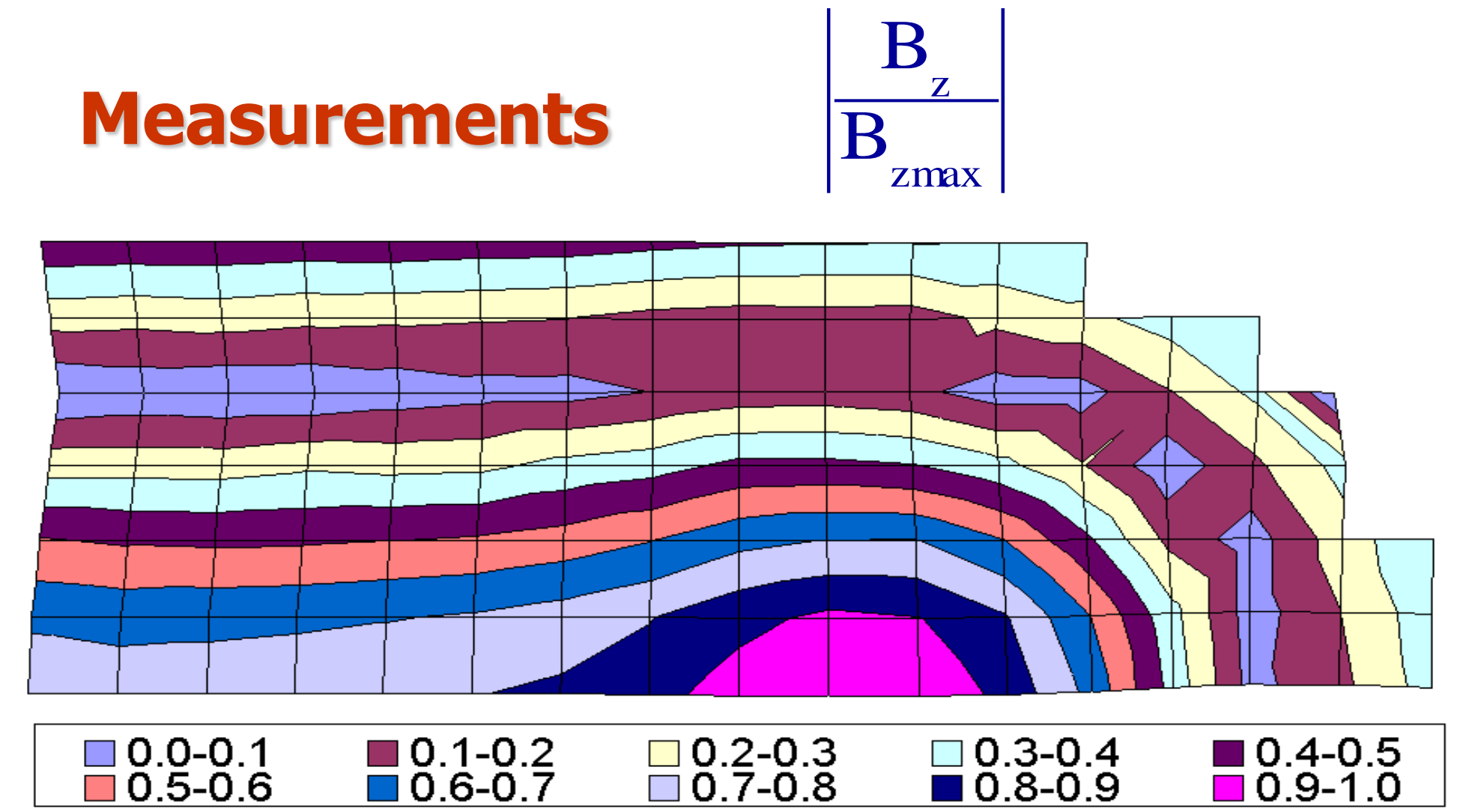


➤ Magnetic field generated by the magnetron determined by a standard finite element method with Femlab 2.3.®

Model results

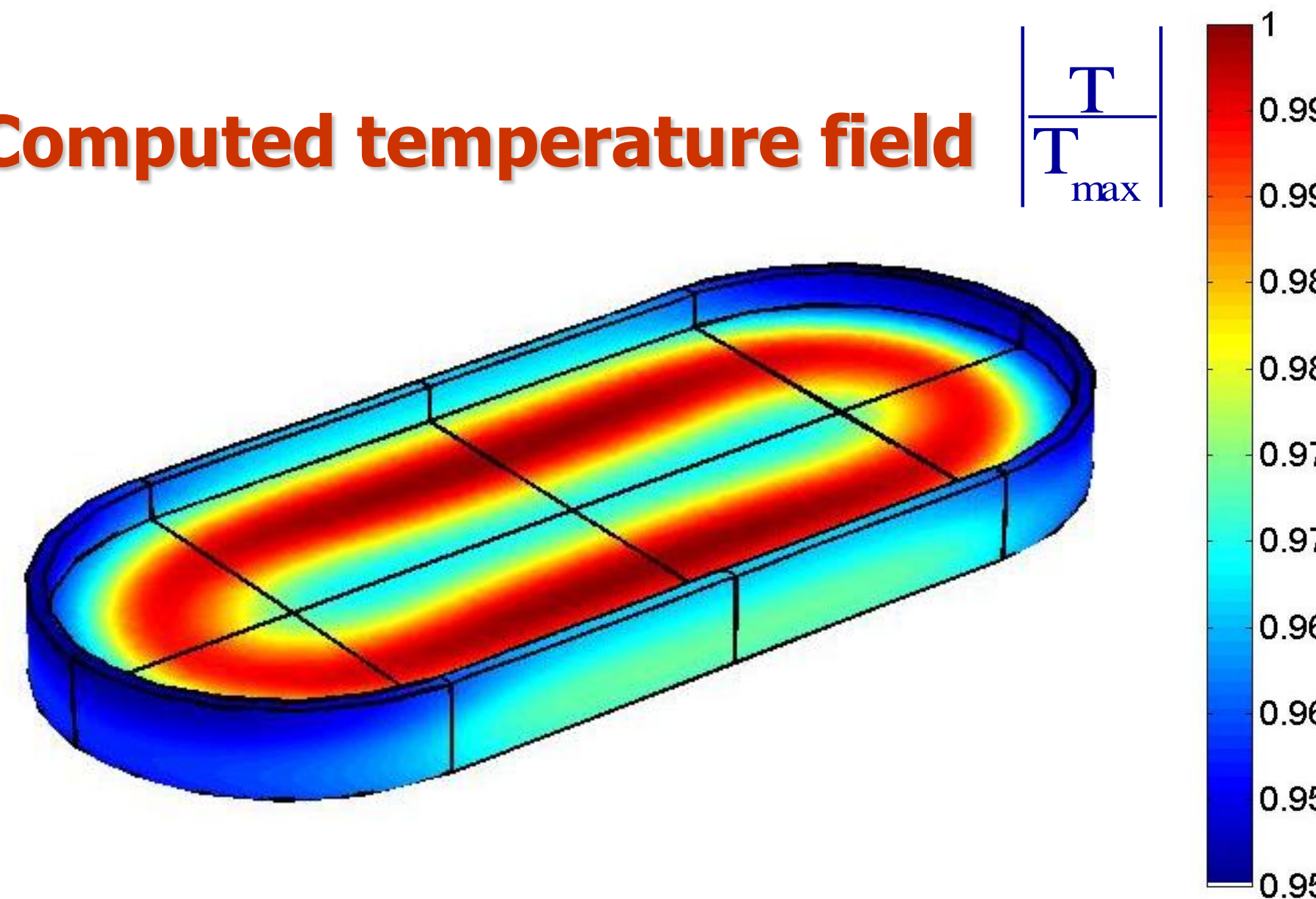


Measurements



➤ Creation of a specific Matlab® module to compute radiative heat transfer using the zone method
➤ Coupling with standard finite element conduction model of Femlab 2.3.®

Computed temperature field



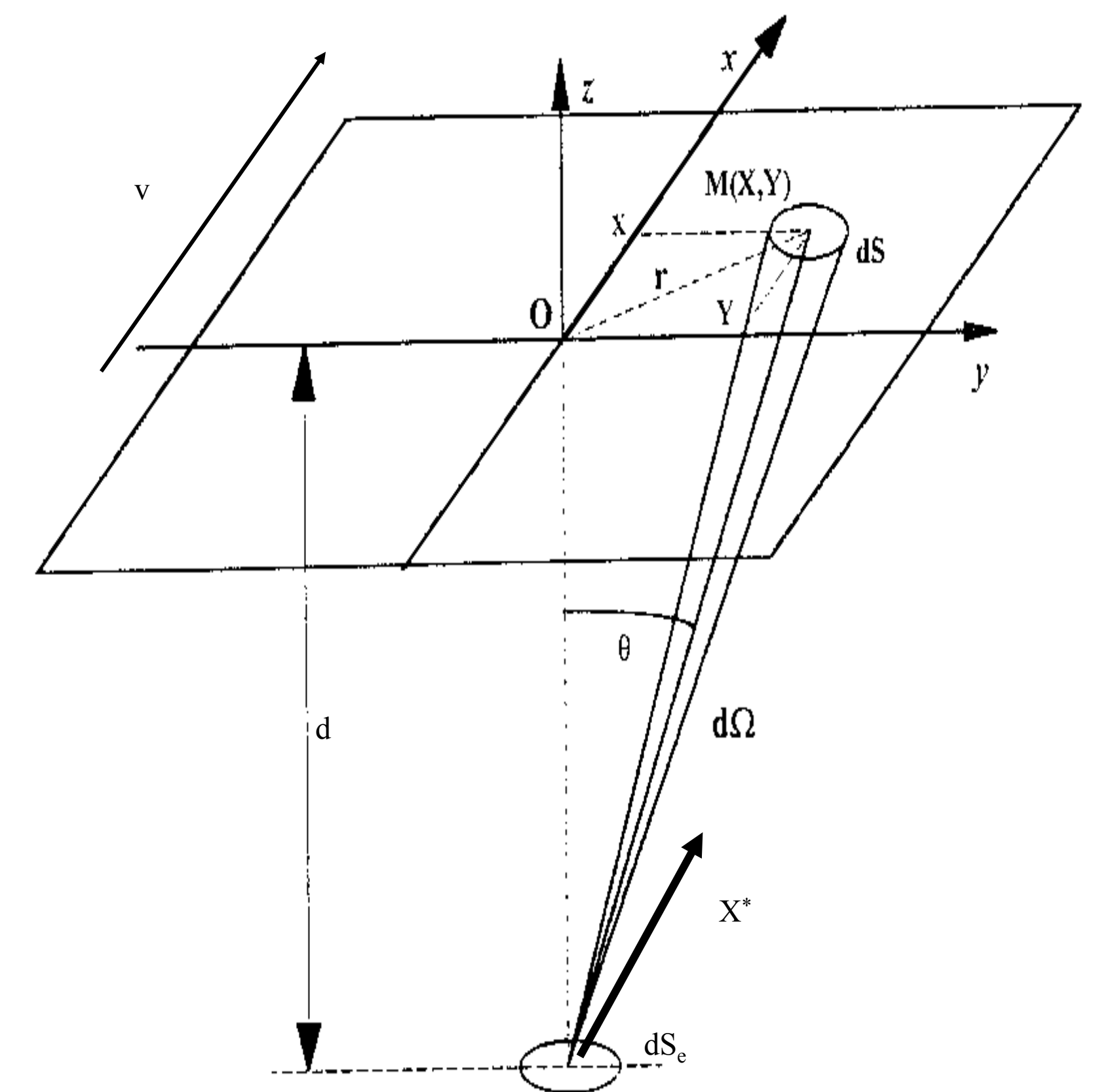
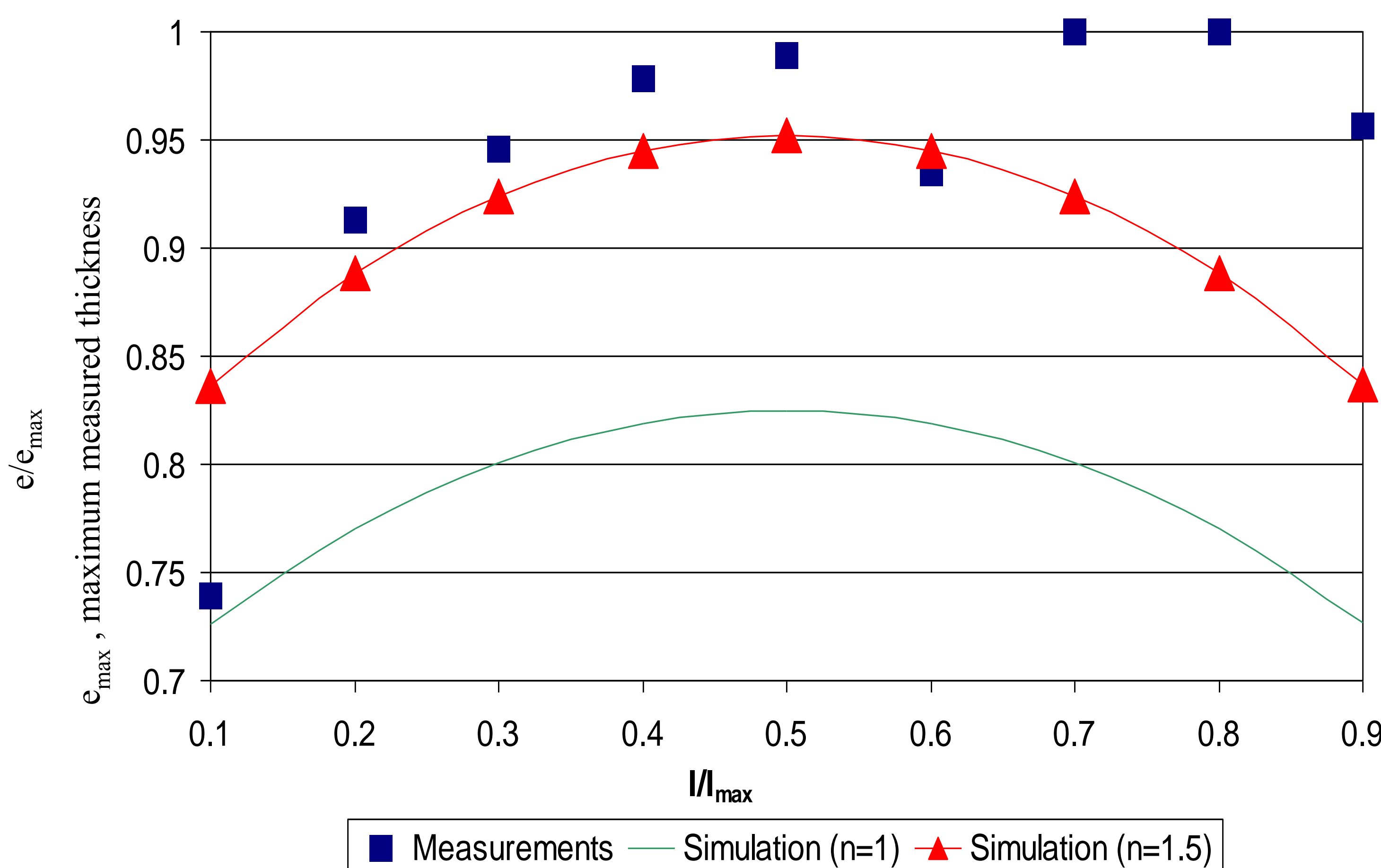
Picture of the target



➤ Thickness profile obtained on the substrate given by $e(X,Y) = \int_0^{\infty} \frac{J_d(x^*,y)}{\rho_e} d\tau$ with $x^* = v\tau$

$$J_d = \int_{S_e} \frac{(n+1)J_e}{2\pi} \frac{d^{(n+1)}}{(r^2+d^2)^{\frac{(n+3)}{2}}} dS_e \quad \text{and} \quad J_e = 5,834 \cdot 10^{-1} \sqrt{\frac{M_t}{T_e}} (p_v - p_{stat})$$

ρ_e , density of evaporated material - v , velocity of the substrate - τ , the time - $J_{d(e)}$, deposited (evaporated) mass flux - $P_{v(stat)}$, vapour (static) pressure (Torr) - M_t , molecular mass of the target material



Conclusions

No perfect agreement between measured and computed results because of

• probable measurements errors

⇒ New series of tests projected

• simplifying assumptions introduced into the model

⇒ Modifications of the model in progress